

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 04-175299

(43)Date of publication of application : 23.06.1992

(51)Int.Cl. C30B 29/68
C30B 25/02
C30B 29/40
// H01L 21/205

(21)Application number : 02-302632

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(22)Date of filing : 09.11.1990

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(54) COMPOUND SEMICONDUCTOR CRYSTAL GROWTH AND COMPOUND SEMICONDUCTOR DEVICE

(57)Abstract:

PURPOSE: To produce a compound semiconductor layer having hetero interfaces so as to acquire such steep hetero interfaces as to have a precision of monatomic layer, by feeding, using the atomic layer epitaxy technique, a semiconductor substrate with the feedstocks of elements constituting the title compound semiconductor in high flow rate at low-growth temperature and low-growth pressure.

CONSTITUTION: Using the atomic layer epitaxy technique, a semiconductor substrate is alternately fed with the feedstocks of elements constituting the objective compound semiconductor to effect monatomic layer growth of the superlattice structure layer of (GaAs)_m(GaP)_n, (GaAs)_m(GaAsP)_n, (GaAsP)_m(GaP)_n or (GaAs)_l(GaAsP)_m(GaP)_n (l, m and n are each positive integer). It is preferable that the feedstocks for Ga, As and P be trimethylgallium, arsine and phosphine, respectively, and said semiconductor substrate be fed with the trimethylgallium in high flow speed at low-growth temperature and pressure to effect monatomic layer growth through decomposition reaction on said substrate's surface.

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]